

L Number	Hits	Search Text	DB	Time stamp
441	22	composite near2 "etch stop"	USPAT; EPO; JPO; IBM_TDB	2002/11/06 13:22
444	341	composite same "etch stop"	USPAT; EPO; JPO; IBM_TDB	2002/11/06 14:04
445	44	"dual damascene" and (composite same "etch stop")	USPAT; EPO; JPO; IBM_TDB	2002/11/06 14:05
446	304	"dual damascene" same "etch stop"	USPAT; EPO; JPO; IBM_TDB	2002/11/06 14:10
450	1542	"dual damascene"	USPAT; EPO; JPO; IBM_TDB	2002/11/06 15:02
451	190	"silicon oxide" same "silicon nitride" same "silicon oxynitride" same PECVD	USPAT; EPO; JPO; IBM_TDB	2002/11/06 15:28
456	120	("silicon oxide" or "SiO.sub.2") same ("silicon oxynitride" or SiON) same ("etch stop" or barrier)	USPAT; EPO; JPO; IBM_TDB	2002/11/06 15:30